§ 468.16 Effluent limitations representing the degree of effluent reduction attainable by the application of the best conventional pollution control technology (BCT). [Reserved]

Subpart B—Beryllium Copper Forming Subcategory

§ 468.20 Applicability; description of the beryllium copper forming subcategory.

This subpart applies to discharges of pollutants to waters of the United States, and introduction of pollutants into publicly owned treatment works from the forming of beryllium copper alloys.

[51 FR 7571, Mar. 5, 1986]

PART 469—ELECTRICAL AND ELECTRONIC COMPONENTS POINT SOURCE CATEGORY

Subpart A—Semiconductor Subcategory

Sec.
469.10 Applicability.
469.11 Compliance dates.
469.12 Specialized definitions.
469.13 Monitoring.
469.14 Effluent limitations representing the degree of effluent reduction attainable by the application of the best practicable control technology currently available (BPT).
469.15 Effluent limitations representing the degree of effluent reduction attainable by the application of the best available technology economically achievable (BAT).
469.16 Pretreatment standards for existing sources (PSES).
469.17 New source performance standards (NSPS).
469.18 Pretreatment standards for new sources (PSNS).
469.19 Effluent limitations representing the degree of effluent reduction attainable by the application of the best conventional pollution control technology (BCT).

Subpart B—Electronic Crystals Subcategory

469.20 Applicability.
469.21 Compliance dates.
469.22 Specialized definitions.
469.23 Monitoring.
469.24 Effluent limitations representing the degree of effluent reduction attainable by the application of the best practicable control technology currently available (BPT).
469.25 Effluent limitations representing the degree of effluent reduction attainable by the application of the best available technology economically achievable (BAT).
469.26 Pretreatment standards for existing sources (PSES).
469.27 New source performance standards (NSPS).
469.28 Pretreatment standards for new sources (PSNS).
469.29 Effluent limitations representing the degree of effluent reduction attainable by the application of the best conventional pollution control technology (BCT).

Subpart C—Cathode Ray Tube Subcategory

469.30 Applicability.
469.31 Specialized definitions.
469.32 Monitoring requirements.
469.34 Pretreatment standards for existing sources (PSES).
469.35 New source performance standards (NSPS).
469.36 Pretreatment standards for new sources (PSNS).

Subpart D—Luminescent Materials Subcategory

469.40 Applicability.
469.41 Specialized definitions.
469.42 New source performance standards (NSPS).
469.43 Pretreatment standards for new sources (PSNS).

AUTHORITY: Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, as amended by the Clean Water Act of 1977, 33 U.S.C. 1311, 1314, 1316, 1317, 1318, and 1361; 86 Stat. 816, Pub. L. 92–500; 91 Stat. 1567, Pub. L. 95–217, unless otherwise noted.

SOURCE: 48 FR 15394, Apr. 8, 1983, unless otherwise noted.

Subpart A—Semiconductor Subcategory

§ 469.10 Applicability.

The provisions of this subpart are applicable to discharges resulting from all process operations associated with the manufacture of semiconductors, except sputtering, vapor deposition, and electroplating.